



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Attorney Docket No. OMY-010

In re patent application of

Masami AKIMOTO, *et al.*

Serial No. 09/855,806

Filed: May 16, 2001

Title: FILM FORMING APPARATUS AND FILM FORMING METHOD

Confirmation No.: 1549

Group Art Unit: 1763

Examiner: Anna M. Crowell

AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Sir:

In response to the non-final Office Action dated November 20, 2002, please amend the above-identified application as follows:

In the Claims:

In accordance with 37 CFR 1.121 (c)(1)(i), please rewrite claims 1 and 12 as set forth below in clean form. Additionally, in accordance with 37 CFR 1.121(c)(1)(ii), amended claims 1 and 12 are set forth in a marked-up version in the pages attached to this Amendment.

1. (twice-amended) An apparatus, comprising:
 - a polishing chamber for polishing a conductive film which is formed on a substrate;
 - a cleaning chamber for cleaning the polished substrate polished in the polishing chamber;
 - at least one drying chamber, having a first transferring port and a second transferring port, for drying the cleaned substrate transferred from the cleaning chamber through the first transferring port under a reduced pressure;
 - a film forming chamber for forming a thin film on the substrate by a CVD method under the reduced pressure;

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